

520.39737X00

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s):

T. OTSUBO

Serial No.:

09/842,000

Filed:

April 26, 2001

For:

PLASMA PROCESSING APPARATUS AND PROCESSING

**METHOD** 

Group:

1763

Examiner:

A. Crowell

## **AMENDMENT**

Commissioner for Patents Washington, D.C. 20231

March 20, 2003

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Sir:

The following amendments and remarks are respectfully submitted in connection with the above-identified application in response to the Office Action dated December 20, 2002.

## IN THE SUBSTITUTE SPECIFICATION:

Page 27, please amend the paragraph beginning at line 8 as follows:

Radio frequency power is applied to the stage electrode 3 from the bias power supply 17 through transformer 29. Radio frequency current passes through the substrate 15 and the plasma, and flows to facing electrodes 2a and 2b. Since the transformer 29 is separated from or is floated with respect to the ground, almost all the radio frequency current flowing from the stage electrode 3 is fed to facing electrodes 2a and 2b, without going to any other places.

Page 28, please amend the paragraph beginning at line 13 as follows:

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	Patent ☐         Trademark ☐         503.39737X00           Serial No09/842,000         FiledApril _ 26, _ 2001           Applicant(s)T. OTSUBO	
	Papers filed herewith on November 29, 2001    Fees \$	
~-	of Original Specification & Abstract  Receipt is hereby acknowledged of the papers filed as indicated in connection with above identified case.  COMMISSIONER OF PATENTS AND TRADEMARKS	
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